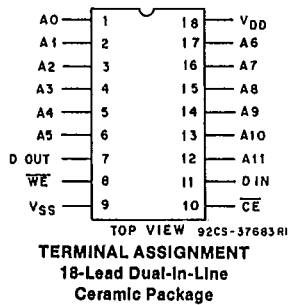


CMM5104/3 CMM5104/3Z

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High-Reliability, Radiation-Hardened CMOS/SOS 4096-Word by 1-Bit LSI Static RAM

Radiation Features:

- Manufactured on 100K rads (Si) production line
- Cosmic ray upset immunity typically 2×10^{-9} errors/bit day
- Latch-up free under transient radiation
- Transient upset $> 10^{10}$ rads/sec, 20-ns pulse

Features:

- Fully static operation
- Single power supply: 4.5 V to 6.5 V
- All inputs and outputs TTL compatible
- 3-state outputs
- Industry-standard 18-pin configuration
- Fast access time: $t_{AVQ} = 200$ ns
- Low standby and operating power

Package Specifications

See Section 11, Fig. 3, b1

The RCA-CMM5104/3 and CMM5104/3Z are high-reliability 4096-word by 1-bit static random-access memories using CMOS/SOS technology. These devices are designed for use in memory systems where low power and simplicity in use are desirable.

CMOS/SOS technology permits operation in high-radiation environments. It is insensitive to neutrons, cannot latch up at any dose rate and is resistant to single-event upset caused by cosmic rays or heavy ions.

TTL compatibility on all input and output terminals permits easy system integration. The data-out signal has the same polarity as the input data. A separate data input and a separate tri-state output are used.

The CMM5104/3 and CMM5104/3Z are supplied in a 18-lead dual-in-line side-brazed ceramic package (D suffix). The parts are also available in a 24-lead flat-pack ceramic package (K suffix), and in a 24-terminal leadless ceramic chip package (J suffix).

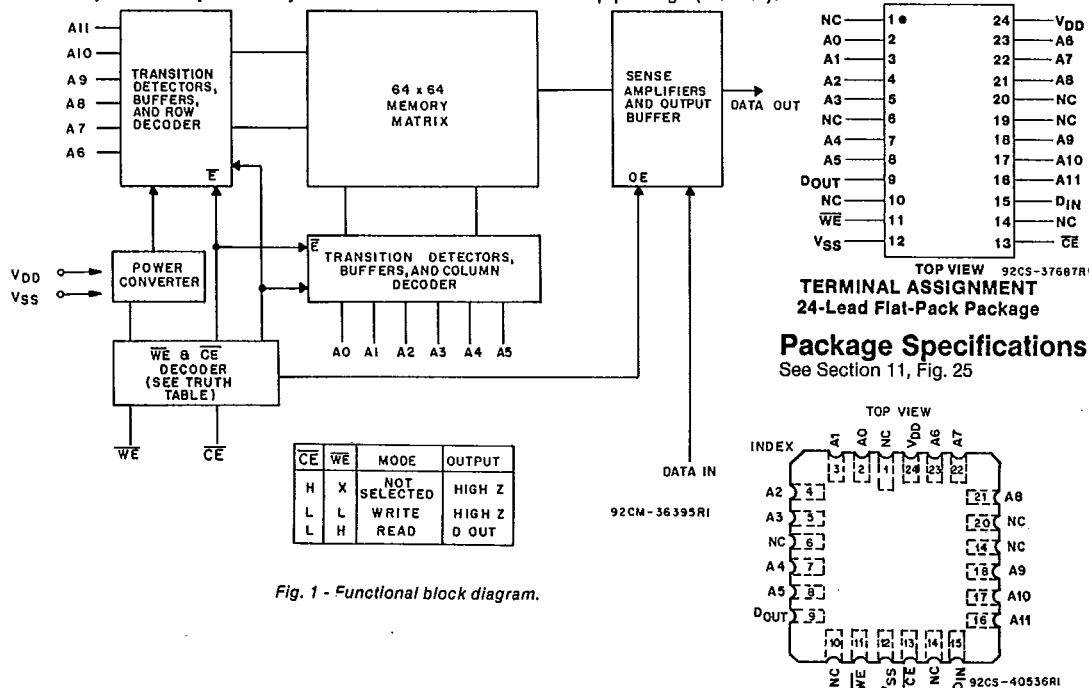


Fig. 1 - Functional block diagram.

Package Specifications

See Section 11, Fig. 34, c1

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CMM5104/3
CMM5104/3Z**MAXIMUM RATINGS, Absolute-Maximum Values:**DC SUPPLY-VOLTAGE RANGE, (V_{DD}):(All voltage values referenced to V_{SS} terminal) -0.5 to +7 VINPUT VOLTAGE RANGE, ALL INPUTS -0.5 to $V_{DD} + 0.5$ VDC INPUT CURRENT, ANY ONE INPUT ± 10 mAPOWER DISSIPATION PER PACKAGE (P_D):For $T_A = -55$ to $+100^\circ\text{C}$ 500 mWFor $T_A = +100$ to $+125^\circ\text{C}$ Derate Linearly at 12 mW/ $^\circ\text{C}$ to 200 mW

DEVICE DISSIPATION PER OUTPUT TRANSISTOR

For $T_A = \text{FULL PACKAGE-TEMPERATURE RANGE}$ 100 mWOPERATING-TEMPERATURE RANGE (T_A) -55 to $+125^\circ\text{C}$ STORAGE TEMPERATURE RANGE (T_{stg}) -65 to $+150^\circ\text{C}$

LEAD TEMPERATURE (DURING SOLDERING FOR D AND K PACKAGE TYPES):

At distance $1/16 \pm 1/32$ in. (1.59 ± 0.79 mm) from case for 10 s max. $+265^\circ\text{C}$

OPERATING CONDITIONS at $T_A = -55^\circ\text{C}$ to $+125^\circ\text{C}$. For maximum reliability, operating conditions should be selected so that operation is always within the following ranges:

CHARACTERISTIC	LIMITS		UNITS
	MIN.	MAX.	
DC Operating Voltage Range	4.5	6.5	V

STATIC ELECTRICAL CHARACTERISTICS, $V_{DD} = 5\text{ V} \pm 5\%$, $V_{IN} = 0\text{ V}$ or V_{DD} , Except as Noted

CHARACTERISTIC		TEST CONDITIONS	LIMITS						UNITS
			+25° C		-55° C/+125° C		POST RADIATION‡ +25° C		
			MIN.	MAX.	MIN.	MAX.	MIN.	MAX.	
Quiescent Device Current	I _{DD}	—	—	0.1*	—	1*	—	1*	mA
Operating Device Current	I _{OPR} *	—	—	4.5	—	4.5	—	4.5	
Operating Device Current (Deselected)	I _{OPRD}	—	—	0.1	—	1	—	1	
Output Low Drive (Sink) Current	I _{DN}	V _{OUT} =0.4 V	4*	—	2.5*	—	2.5*	—	
Output High Drive (Source) Current	I _{DP}	V _{OUT} = V _{DD} -0.4 V	3*	—	2*	—	2*	—	
Output Voltage Low Level	V _{OL}	—	—	0.1	—	0.1	—	0.1	V
Output Voltage High Level	V _{OH}	—	V _{DD} -0.1	—	V _{DD} -0.1	—	V _{DD} -0.1	—	
Input Low VoltageΔ	V _{IL}	—	—	0.8*	—	0.8*	—	0.8*	
Input High VoltageΔ	V _{IH}	—	V _{DD} /2*	—	V _{DD} /2*	—	V _{DD} /2*	—	
Input Leakage Current	I _{IN}	—	—	±2*	—	±10*	—	±10*	μA
3-State Output Leakage Current	I _{OZ}	—	—	±5*	—	±30*	—	±30*	
Input Capacitance§	C _{IN}	—	—	5	—	5	—	5	pF
Output Capacitance§	C _{OUT}	—	—	7	—	7	—	7	

†Radiation measurements are made on 2 samples/wafer. The limits shown are for within 1 hour of radiating to 100K rads (Si).

Limit with black dot () designates actual measurement, all other limits are inherent design characteristics.

Δ Operating current measured using 1-MHz cycle and $C_L = 50\text{ pF}$.

Δ Measured using 1-MHz cycle.

\S Capacitance measurements are made with no bias applied.

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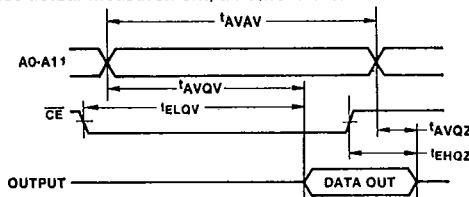
CMM5104/3Z

DYNAMIC ELECTRICAL CHARACTERISTICS, $V_{DD} = 5V \pm 5\%$, $C_L = 50\text{ pF}$

CHARACTERISTIC	LIMITS						UNITS
	+25° C		-55° C/+125° C		POST RADIATION† +25° C		
	MIN.	MAX.	MIN.	MAX.	MIN.	MAX.	
Read-Cycle Times (Fig. 2)							
Read Cycle	t _{AVAV}	200	—	250	—	250	—
Access From Address	t _{AVQV}	—	200*	—	250*	—	250*
Access From \overline{CE}	t _{ELQV}	—	220*	—	280*	—	280*
Output Hold From Address	t _{AVOZ}	—	80	—	100	—	100
Output Hold From \overline{CE}	t _{EHQZ}	—	80	—	100	—	100

†Radiation measurements are made on 2 samples/wafer. The limits shown are for within 1 hour of radiating to 100K rads (Si).

Limit with black dot () designates actual measurement, all other limits are inherent design characteristics.

TIMING MEASUREMENT IS REFERENCED TO $V_{DD}/2$.

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Fig. 2 - Read-cycle timing waveforms.

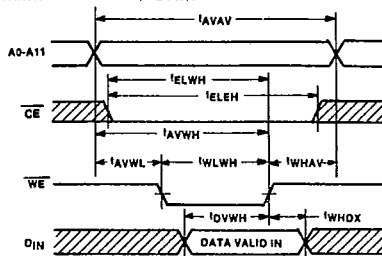
DYNAMIC ELECTRICAL CHARACTERISTICS, $V_{DD} = 5V \pm 5\%$, $C_L = 50\text{ pF}$

CHARACTERISTIC		LIMITS						UNITS
		+25°C		-55°C/+125°C		POST RADIATION‡ +25°C		
		MIN.	MAX.	MIN.	MAX.	MIN.	MAX.	
Write-Cycle Times (Fig. 3)								
Write Cycle	t _{AVAV}	200*	—	250*	—	250*	—	ns
Write Pulse Width	t _{WLWH} *	125*	—	145*	—	145*	—	
Address Set-up to Beginning of Write	t _{AVWL}	0*	—	0*	—	0*	—	
Address Set-up to End of Write	t _{AVWH}	160*	—	205*	—	205*	—	
Address Hold Time	t _{WHAV}	40*	—	45*	—	45*	—	
CE to Write Set-up Time	t _{ELWH}	160*	—	205*	—	205*	—	
CE Pulse Width	t _{ELEH} *	180*	—	220*	—	220*	—	
Data to Write Set-up Time	t _{DVWH}	100*	—	120*	—	120*	—	
Data Hold From Write	t _{WHDX}	5*	—	10*	—	10*	—	

†Radiation measurements are made on 2 samples/wafer. The limits shown are for within 1 hour of radiating to 100K rads (Si).

Limit with black dot () designates actual measurement, all other limits are inherent design characteristics.

* \overline{CE} and \overline{WE} must overlap for at least t_{WLWH} min. value, t_{DVWH} min. value must occur during this overlap.

TIMING MEASUREMENT IS REFERENCED TO $V_{DD}/2$.

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* \overline{CE} and \overline{WE} MUST OVERLAP FOR AT LEAST t_{WLWH} MIN. VALUE,
 t_{DVWH} MIN. VALUE MUST OCCUR DURING THIS OVERLAP.

Fig. 3 - Write-cycle timing waveforms.

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DATA RETENTION CHARACTERISTICS

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CHARACTERISTIC	TEST CONDITIONS	LIMITS						UNITS
		+25°C		-55°C/+125°C		POST RADIATION‡ +25°C		
		MIN.	MAX.	MIN.	MAX.	MIN.	MAX.	
See Fig. 4	V _{DD} (V)							
Minimum Data Retention Voltage V _{DR}	—	—	2*	—	2.5*	—	2.5*	V
Data Retention Quiescent Current I _{DDDR}	—	—	40*	—	400*	—	400*	μA
V _{DD} to V _{DR} Rise and Fall Time t _r , t _f	5	1	—	1	—	1	—	μs

†Radiation measurements are made on 2 samples/wafers. The limits shown are for within 1 hour of radiating to 100K rads (Si).

Limit with black dot () designates actual measurement, all other limits are inherent design characteristics.

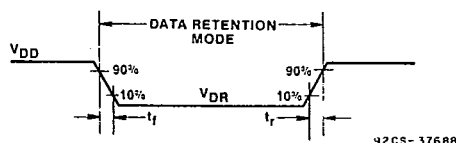
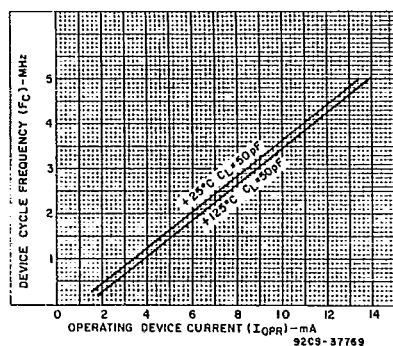
Fig. 4 - Low V_{DD} data retention timing waveforms.

Fig. 5 - Typical operating device-current (selected) as a function of cycle frequency.

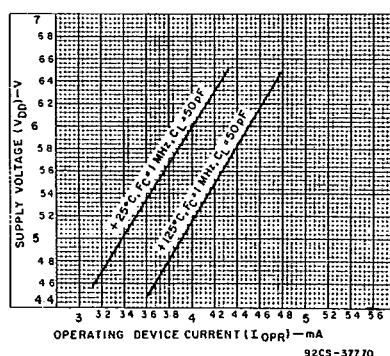
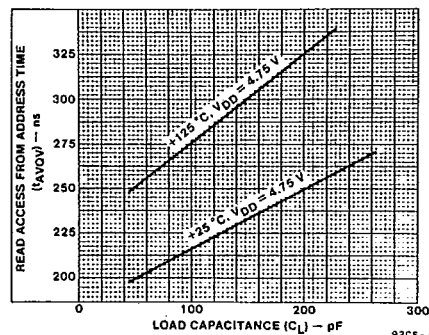


Fig. 6 - Typical operating device-current (selected) as a function of supply voltage.

Fig. 7 - Read access from address time (t_{AVOV}) as a function of load capacitance. (Time measurements made at 50% V_{DD} point.)

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/3Z SCREENING FLOW

Radiation Verification Method 1019 - 100K rads (Si) Total Dose
2 samples/wafer, 0 rejects
(/3Z Screening continues below)

/3 SCREENING FLOW (Without Radiation Verification)

Internal Visual (100%) Method 2010 - Condition B (Modified) - See Note 1
Pre-Seal Bake (100%)
Stabilization Bake (100%) Method 1008 - Condition C 24 hrs., 25°C
No End-Point Measurements Required
Temperature Cycling (100%) Method 1010 - Condition C
Constant Acceleration (100%) Method 2001 - Condition E₁, Y₁ Direction, Centrifuge
Seal:
Fine (100%) Method 1014 - Condition A or B
Gross (100%) Method 1014 - Condition C
Initial Electrical Tests (100%) Per Applicable Device Specification, 25°C
High-Temperature Stress (100%) 48 hrs, 125°C, See Table II
Interim Electrical Tests I (100%) Per Applicable Device Specifications, 25°C
PDA 10% all tests. See Table I.
Static Burn-In (100%) 160 hrs, 125°C, See Table II
Interim Electrical Tests II (100%) Per Applicable Device Specifications, 25°C
PDA 5% all tests, PDA 3% Functional, See Table I
Final Electrical Tests (100%) Per Applicable Device Specifications, 25°C
External Visual (100%) Method 2009
Quality Conformance
Group A (All Tests) Method 5005 (Class B), See Table I
Group B (Optional) Method 5005 (Class B), See Table I
Group C (Optional) Method 5005 (Class B), See Table I
Group D (Optional) Method 5005 (Class B), See Table I

TABLE I - ELECTRICAL TESTS

Post Radiation See STATIC and DYNAMIC Characteristics (Post Radiation, 25°C)
Initial Electrical Tests Same as above (25°C)
Interim Electrical Tests I Same as above (25°C)
Interim Electrical Tests II Same as above (25°C)
Final Electrical Tests Same as above (-55°C, 25°C, 125°C)
Quality Conformance:
Group A Same as above (-55°C, 25°C, 125°C)
Group B Same as above (25°C)
Group D Same as above (25°C)

TABLE II - BURN-IN AND LIFE-TEST CIRCUITS AND TIMING WAVEFORMS

TEST	TEMPERATURE	DURATION	V _{DD}
Stress	125°C	48 hrs.	7 V
Static	125°C	160 hrs.	7 V
Life Test	125°C	1000 hrs.	5.5 V Min.

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ALL INPUTS ARE CONNECTED THROUGH A 1 TO 6-K Ω RESISTOR TO THE FOLLOWING:

Test Package	STRESS ^c			STATIC ^c			LIFE TEST ^a		
	D	J	K	D	J	K	D	J	K
Pin No.									
1	V _{SS}	—	—	V _{SS}	—	—	A ₀	—	—
2	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₁	A ₀	A ₀
3	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₂	A ₁	A ₁
4	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₃	A ₂	A ₂
5	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₄	A ₃	A ₃
6	V _{SS}	—	—	V _{SS}	—	—	A ₅	—	—
7	—	V _{SS}	V _{SS}	—	V _{SS}	V _{SS}	—	A ₄	A ₄
8	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	ϕ_1	A ₅	A ₅
9	V _{SS}	—	—	V _{SS}	—	—	V _{SS}	—	—
10	V _{SS}	—	—	V _{SS}	—	—	A ₁₃	—	—
11	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₁₂	ϕ_1	ϕ_1
12	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₁₁	V _{SS}	V _{SS}
13	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₁₀	A ₁₃	A ₁₃
14	V _{SS}	—	—	V _{SS}	—	—	A ₉	—	—
15	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₈	A ₁₂	A ₁₂
16	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₇	A ₁₁	A ₁₁
17	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	V _{SS}	A ₆	A ₁₀	A ₁₀
18	V _{DD}	V _{SS}	V _{SS}	V _{DD}	V _{SS}	V _{SS}	V _{DD}	A ₉	A ₉
19	—	—	—	—	—	—	—	—	—
20	—	—	—	—	—	—	—	—	—
21	—	V _{SS}	V _{SS}	—	V _{SS}	V _{SS}	—	A ₈	A ₈
22	—	V _{SS}	V _{SS}	—	V _{SS}	V _{SS}	—	A ₇	A ₇
23	—	V _{SS}	V _{SS}	—	V _{SS}	V _{SS}	—	A ₆	A ₆
24	—	V _{DD}	V _{DD}	—	V _{DD}	V _{DD}	—	V _{DD}	V _{DD}

^aThe following timing waveforms are used for the Dynamic and Life Tests.

^cMemory array is pre-initialized with all 0's.

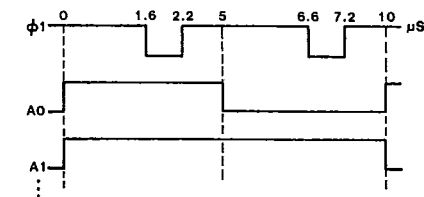
NOTE:

Pin 7 on D-type package, and Pin 9 on J and K packages are the outputs connected to V_{DD}/2 in High Z state.

— indicates no connection.

ϕ_1 is connected to WE on all packages (D, J, and K).

A₁₃ is connected to CE on all packages (D, J, and K).



A1 TO A13 ARE SUCCESSIVE DIVISIONS BY 2 BASED ON A0
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Fig. 8 - Burn-in circuit timing waveforms.

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NOTES:

1. Internal Visual Inspection Modified for LSI

Internal Visual Inspection is performed to MIL-STD-883, Method 2010, Condition B except as follows:

- A. **High magnification inspection** is performed at 200X to 300X and applies to the high current areas of the chip. The remainder of the chip is inspected at 75X to 150X where high magnification is required.
- B. **Metallization Voids** (3.2.1.2) Criteria 3.2.1.1a Metallization Scratches and 3.2.1.2a Metallization Voids shall also apply to metallization over a passivation step (3.2.1.1d, 3.2.1.2b). Underlying oxide must also be exposed.
- C. **Metallization Alignment** (3.2.1.7) Diffusion and Passivation Layer(s) Faults (3.2.0).

High magnification inspection is performed at 200X to 300X, applied to the center and two opposite corners of the chip, consisting only of the area exposed to the immediate field of view.

D. Scribing and Die Defects (3.2.3) In addition:

A crack that exceeds 5 mils in length must also point towards or cross a scribe grid line to be unacceptable.

Semicircular cracks that point away from the active circuit area are acceptable.

2. SOS Technology Devices;

- A. Diffusion faults are not applicable. SOS devices are inspected for complete islands, bridging between islands and missing adjacent contacts from a row in a contact chain.
- B. The 1-mil wire clearance criteria is not applicable.
- C. Passivation faults are not applicable because a second free flow oxide is used prior to metallization.
- D. Oxide gate bridge inspection is not applicable.
- E. Semicircular cracks not in an active area which start and end at the pellet edge are acceptable.